AMENDMENTS TO THE SPECIFICATION

Amend the specification by inserting before the first line the sentence:

This is a divisional of Application No. 10/075,761 filed February 15, 2002; the disclosure of which is incorporated herein by reference.

Amend the specification at page 1, second paragraph as follows:

An organic electroluminescent device is a light-emitting device which makes use of a principle that when an electric field is applied to the device, a fluoresent material emits light in response to a charge recombination of holes injected from an anode and electrons from a cathode. Such organic electroluminescent devices have been developed ever since C. W. Tang et al. ~~P~~published "Organic Electroluminescent Diodes", Applied ~~p~~Physics Lett. 51(12), pp. 913-915, September 21, 1987.

Amend the specification at page 4, first paragraph as follows:

According to the present invention, in an organic electroluminescent device, a plurality of striped lower electrodes are formed on an insulating substrate along a first direction, and a plurality of fillers made of amorphous carbon are filled between the lower electrodes. At least one organic thin film layer including an emitting layer is formed on the fillers and the lower electrodes. A plurality of striped upper electrodes are formed on the organic thin film layer along a second direction different from the first direction.

Amend the specification at page 4, second paragraph as follows:

Also, in a method for manufacturing an organic electroluminescent device according to the present invention, a conductive layer is formed along a first direction on an insulating substrate. Then, a photoresist pattern layer having a plurality of striped elements is formed along a first direction on the conductive layer. Then, the conductive layer is etched by a dry etching process using a first plasma gas and using the photoresist pattern layer as an etching mask in a chamber to form striped lower electrodes. Then, an insulating layer is deposited on the photoresist pattern layer and on the insulating substrate between the lower electrodes by a plasma deposition process using a second plasma gas in the above-mentioned chamber. Then, a lift-off operation is performed upon the photoresist pattern layer to remove the photoresist pattern layer and a part of the insulating layer on the photoresist pattern layer. Then, at least one organic thin film layer including an emitting layer is formed on the insulating layer and the lower electrodes. Finally, a plurality of striped upper electrodes are formed on the organic thin film layer along a second direction different from the first direction.

Amend the specification at page 9, second full paragraph as follows:

There is no particular limitation on a material for the ~~electron-transporting~~electron-transporting layer 17(27). Any ordinary electron-transporting material may be used. For example, the electron-transporting layer 17(27) is made of an oxadiazole derivative such as 2-(4-biphenyl)-5-(4-t-butyrphenyl)-1, 3, 4-oxadiazole derivative (see Fig. 4A) or bis {2-(4-t-butryphenyl)-1, 3, 4-oxadiazole}-m-phenylene (see Fig. 4B), a triazole derivative (see Figs. 4C

and 4D), a quinolinol metal complex (see Figs. 4E, 4F, 4G and 4H), bathophenanthroline (see Fig. 4I), or bathocuprolene (see Fig. 4J).